

AMENDMENTS TO THE CLAIMS:

Please amend Claims 1 and 3, and add Claim 11, as follows:

1. (Currently Amended) An exposure apparatus which draws a pattern on a substrate with electron beams, said apparatus comprising:

- a substrate stage which supports the substrate;
- a transfer stage which moves ~~with~~ said substrate stage ~~on board~~;
- an electromagnetic actuator which moves said substrate stage relative to said transfer stage;
- a first measurement system which measures a position of said transfer stage;
- a second measurement system which measures a position of said substrate stage;
- a controller which controls said electromagnetic actuator on the basis of measurement results obtained by said first and second measurement systems;
- a deflector which deflects electron beams with which the substrate is irradiated; and
- a filter which performs filtering for a measurement result obtained by said second measurement system and supplies the filtered measurement result to said deflector.

2. (Original) The apparatus according to claim 1, wherein

said second measurement system measures rotation of said substrate stage in addition to the position of said substrate stage, and

said deflector adjusts deviations of electron beams on the basis of the position and rotation of said substrate stage obtained by said second measurement system.

3. (Currently Amended) The apparatus according to claim 1, wherein said second measurement system includes:  
a first sensor which measures a position of said substrate stage with reference to a predetermined reference ~~position~~, position; and  
a second sensor which measures a position of said substrate stage relative to said transfer stage,  
wherein said controller controls said electromagnetic actuator on the basis of measurement results obtained by said first measurement system and the second sensor, and  
said filter performs filtering for a measurement result obtained by ~~the~~ said first sensor to supply the filtered measurement result to said deflector.

4. (Original) The apparatus according to claim 3, wherein said second sensor is arranged to measure a relative position of said substrate stage in the vicinity of said electromagnetic actuator.

5. (Original) The apparatus according to claim 1, wherein said substrate stage has a substrate holder on said substrate stage, said electromagnetic actuator and the substrate are arranged on opposite sides of a barycenter of said transfer stage in a Z-axis direction.

6. (Original) The apparatus according to claim 1, wherein said filter includes a band-limiting filter which blocks a predetermined band.

7. (Original) The apparatus according to claim 1, wherein said electromagnetic actuator includes an electromagnet as a driving source.

8. (Original) The apparatus according to claim 1, wherein said electromagnetic actuator includes a linear motor.

9. (Original) The apparatus according to claim 1, wherein said electromagnetic actuator is coated with an electromagnetic shield.

10. (Original) A device manufacturing method comprising:  
a step of drawing a pattern on a substrate coated with a photosensitive agent using an exposure apparatus as defined in claim 1; and  
a step of developing the substrate.

11. (New) An exposure apparatus which draws a pattern on a substrate with electron beams, said apparatus comprising:

a substrate stage which supports the substrate;  
a transfer stage which moves said substrate stage;  
an electromagnetic actuator which moves said substrate stage relative to said transfer stage;  
first measurement means for measuring a position of said substrate stage relative to a reference position;

second measurement means for measuring a position of said substrate stage relative to said transfer stage;

third measurement means for measuring a position of said transfer stage;

a controller which controls said electromagnetic actuator on the basis of measurement results obtained by said second measurement means and said third measurement means; and

a deflector which deflects electron beams with which the substrate is irradiated,

wherein said deflector is controlled on the basis of a measurement result obtained by said first measurement means.